→ USPTO GENERAL

Serial No.: 09/848,046

## AMENDMENTS IN THE CLAIMS:

## 1-6. (Canceled)

- 7. (Currently Amended) A method for producing an optical disk master, comprising the steps of:
- (a) providing a substrate having a photoresist film provided on a surface thereof:
  - (b) rotating the substrate in a relative relationship with a beam;
- (c) during a rotation of the substrate, irradiating the photoresist film on the substrate with the beam so as to form a first beam trace in the photoresist film;
- (d) during a rotation which is subsequent to the rotation during which the first beam trace is formed, further irradiating the photoresist film with the same beam such that the beam partially overlaps the first beam trace, so that a second beam trace is formed in the photoresist film; and
- (e) completing the optical disk master using the photoresist film, wherein the second beam trace comprises a data region in a track adjacent to the first beam trace.
- 8. (Original) A method for producing an optical disk master according to claim 7, wherein the step (d) comprises shifting the beam in a radial direction of the substrate and irradiating the photoresist film with the beam so as to form the second beam trace.
- 9. (Original) A method for producing an optical disk master according to claim 7, wherein the step (d) comprises formation of a second beam trace having a width which is larger than a half-value of the width of the beam in the photoresist film.

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- A method for producing an optical disk, (Currently Amended) 10. comprising the steps of:
- providing a substrate having a photoresist film provided on a surface (a) thereof:
  - rotating the substrate in a relative relationship with a beam; (b)
- during a rotation of the substrate, irradiating the photoresist film on the (c) substrate with the beam so as to form a first beam trace in the photoresist film;
- during a rotation which is subsequent to the rotation during which the first (d) beam trace is formed, further irradiating the photoresist film with the same beam such that the beam partially overlaps the first beam trace, so that a second beam trace is formed in the photoresist film;
  - completing an optical disk master using the photoresist film; and (e)
- producing the optical disk using the optical disk master, (g) wherein the second beam trace comprises a data region in a track adjacent to the first beam trace.
- A method for producing an optical disk 11. (Currently Amended) according to claim 7, wherein the first and second beam traces define a deformed portion of a track, wherein the deformed portion that is non-overlapping with an adjacent track trace.
- A method for producing an optical disk (Previously Presented) 12. according to claim 10, wherein the first and second beam traces define a deformed portion of a track, wherein the deformed portion that is non-overlapping with an adjacent track trace.